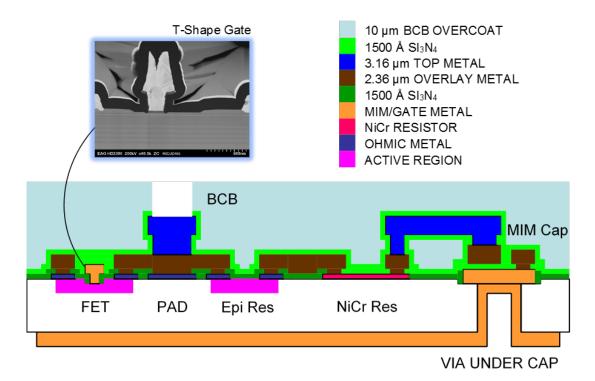


# 0.35 μm GaAs pHEMT – PH6 Foundry Process



## **DESCRIPTION**

PH6 is a 100 mm optical lithography 0.35  $\mu$ m GaAs PH6 is a 100 mm optical lithography 0.35  $\mu$ m GaAs pHEMT process used for low noise and power applications up to Ka-Band. The process features a high breakdown 0.35  $\mu$ m T-gate pHEMT depletion mode FET on a 100  $\mu$ m thick GaAs substrate with through VIA holes. Individual source VIAs are also available. Passives include two thick-metal interconnect layers, NiCr thin film and EPI resistors, MIM capacitors and MIM capacitors on VIA. The process of MIM capacitors on VIA greatly enhance circuit integration and grounding at high frequency. The protective BCB overcoat layer provides environmental robustness and repeatable packaged performances.

Typical Ft at  $V_{DS}$  = 2 V is 51 GHz and typical NF min at 3 V and 50 mA/mm is less than 1 dB at 10 GHz for a 400  $\mu$ m FET.

Simple to use, and highly competitive, PH6 is ideal for both commercial and military mmWave applications up to Ku-Band.

## **FEATURES**

- MIM Capacitors and Capacitors Over VIA
- 20 & 50 Ω/sq NiCr Resistors
- EPI Resistors
- High-Q Passive Devices
- DC Diodes
- ESD Diodes
- Two Thick Metal Interconnects
- Air Bridges
- Substrate VIAs
- BCB Protective Overcoat
- 4 mils Substrate Thickness

#### **APPLICATIONS**

- Up to 18 GHz
- High Power Amplifiers
- Driver Amplifiers
- Low Noise Amplifiers
- Digital & Analog Phase Shifters
- Control Products
- Up/Down Converters
- Multipliers



# 0.35 µm GaAs pHEMT – PH6 Foundry Process (continued)

### **KEY PROCESS PARAMETERS**

Element	Parameter	Nominal Value	Units	Condition
- - FET - -	I <sub>DSS</sub>	250	mA/mm	$V_{GS} = 0 V$ , $V_{DS} = 3 V$
	I <sub>MAX</sub>	520	mA/mm	$I_{GS} = 1 \text{ mA/mm}, V_{DS} = 2 \text{ V}$
	gm	310	mS/mm	$I_{DS} = 50 \% I_{DSS}, V_{DS} = 3 V$
	$V_{BDS}$	22	V	Gate-drain at 1 mA/mm
	$V_{P}$	-1.1	V	$V_{DS} = 3 \text{ V}, I_{DS} = 2.5 \% I_{DSS}$
	FT	23	GHz	$V_{DS} = 8 \text{ V, } I_{DS} = 100 \text{ mA/mm}$
	FT	55	GHz	Peak
MIM Capacitor	Density	400	pF/mm²	_
MIM Capacitor over VIA	_	Yes	_	_
NiCr Resistor	Sheet Resistance	20	Ω/sq	_
	_	50	Ω/sq	_
EPI Resistor	Sheet Resistance	195	Ω/sq	_
Substrate VIA	_	Yes	_	_
Substrate	Thickness	100	μm	_

<sup>4</sup> mils Samples Available upon Request

#### **EXAMPLES OF APPLICATION:**

- MAAP-011068, X-Band 5 W High Power Amplifier:
   This amplifier provides 20 dB of small signal gain,
   5 W saturated output power and 35% efficiency in pulsed mode from 7 to 11 GHz while biased at 9 V. It is ideally suited for both commercial and military radar applications.
- MAMF-011015, X-Band Multifunction Core Chip: This integrated core chip packaged in a 7 x 7 mm surface mount plastic package features a 6-bits phase shifter and a 4-bits attenuator in the common leg, 26 dB and 9 dB of overall gain respectively through the receive and transmit paths. The device is integrated with a CMOS

logic controller within the QFN package. It is ideally suited for commercial radar applications such as early detection and warning for severe impending weather.

• MAMF-011030, Ku-Band TR Module:

This 14 to 15.5 GHz transmitter/receiver module features a 6-bits phase shifter in the common leg, a 4-bits attenuator, 19 dB and 20 dB of overall gain respectively through the receive and transmit paths. It is encapsulated in a 7 x 7 mm surface mount plastic package. It is ideal for both commercial and military Ku-Band communication links.



2.5

1.5 (dB) (dB) NF<sub>MIN</sub> (dB)

0

3.5

3

2.5

1.5

1

0.5

200

(dB)

Gain (dB)

-->-- NF

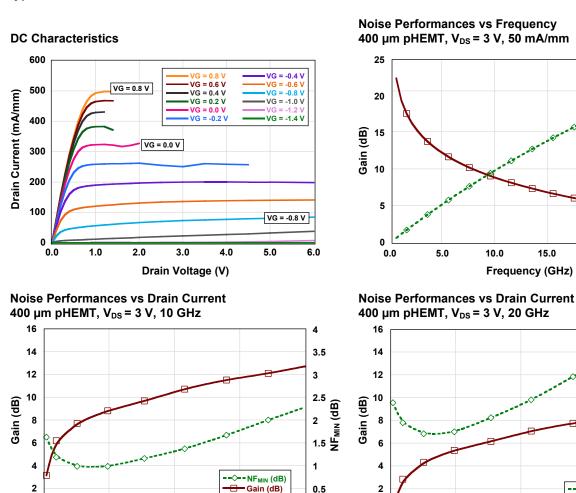
NF<sub>MIN</sub> (dB)

25.0

20.0

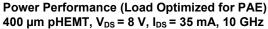
# 0.35 µm GaAs pHEMT – PH6 Foundry Process (continued)

## **Typical Performance Curves**

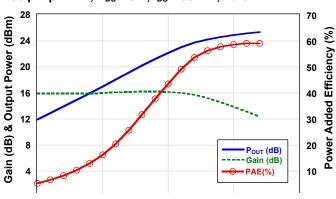


200

0

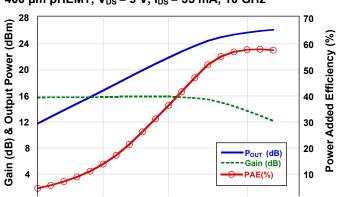


50



Drain Current (mA/mm)

# Power Performance (Load Optimized for PAE) 400 $\mu$ m pHEMT, $V_{DS} = 9 \text{ V}$ , $I_{DS} = 35 \text{ mA}$ , 10 GHz



100

Drain Current (mA/mm)



# 0.35 µm GaAs pHEMT – PH6 Foundry Process (continued)

## **Typical Performance Curves**

